

Guided formation of a Sub-10 nm suicide dot array on an area patterned by electron-beam lithography

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Advanced materials

2007; 19(21):3469-3472

ARTICLE IDENTIFIERS

DOI: 10.1002/adma.200701043

PMID: unavailable

PMCID: not available

JOURNAL IDENTIFIERS

LCCN: 90656517

pISSN: 0935-9648

eISSN: 1521-4095

OCLC ID: 21104347

CONS ID: not available

US National Library of Medicine ID: 9885358

This article was identified from a query of the SafetyLit database.